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## **PATENT**

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FORM PTO-144 (Rev. 7-80)	9 (Mod	dified)	PARENTA	ept. of Commerce Trademark Office	SONY-T0964 (S00P0964US00)			Appln. No. 09/636,053				
(Rev. 7-80)	1	INFORMATION DISCL	OSURE CITATION	Applicant(s) GORO FUJITA								
(Use severa)	sheet	s if necessary)	Filing Date Gr August 10, 2000			Group	7453					
U.S. PATENT DOCUMENTS												
*Examiner Initials		Document Number	Date	Name		Class Subclas		Lass	Filing Date			
NOIN	AA	5,602,810	02/11/97	HORIMAI ET AL.		369 44.34			10/04/95			
401	AB	5,606,545	02/25/97	HORIMAI ET AL.		369	124		09/21/95			
CHA	AC	5,633,854	05/27/97	HORIMAI ET AL.	369	124		08/17/94				
75	AD	5,684,783	11/04/97	HORIMAI ET AL.	369	124		08/17/94				
FOREIGN PATENT DOCUMENTS												
*Examiner Initials		Document Number	Date	Country		Class	Subclass		Transl YES	ation NO		
	OTHER DOCUMENTS											
Examiner Date Considered 6/24/07												
* Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.												

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LIST OF U.S. PATENT APPLICATIONS										
NOT FOR PRINTING  NOT FOR PRINTING  In accordance with MPEP § 609 C(2), the Examiner is respectfully requested to consider the listed applications have been considered.										
Atty. Docket No. SONY-T0964			Appln. No. 09/636,053	Applicant(s) GORO FUJITA		ing Date ust 10, 2000	Group 2 <del>752</del> 2653			
*Examiner Initials			U.S. P	ATENT APPLICATIONS		FILING DATE				
New	AE U.S. PATENT APPLICATION NO: 08/990,878				December 15, 1997					
Examiner				Date Considered						
Note	1/2	Hin	di	6/24/02						

\* Examiner: Initial if application considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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